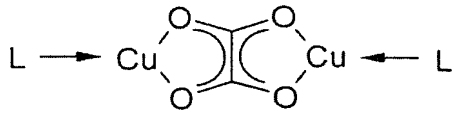
This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Currently amended) A Compound ~~Compounds~~ of ~~the general~~ formula (I)



(I),

in which copper is in the oxidation state +1, and

L is R-C≡C-R' having at least one silyl or ester group, R'HC=CHR having at least one silyl or ester group, R'_3Si-C≡C-R', R'_3N, $R'_2N(CH_2)_nNR'_2$, substituted or unsubstituted 2,2'-bipyridine, 1,10-phenanthroline, $P(OR')_3$, $P(alkyl)_3$, R'-O-R', R'-$O(CH_2)_n$O-R', R'-S-R', R'-$S(CH_2)_n$S-R', ~~or a nitrile from the group consisting of~~ CH_3-C≡N, ^tBu-C≡N, C_4H_9C≡N ~~and~~ or Ph-C≡N,

where

R is A, aryl, alkylaryl or alkynyl having at least one SiR'_3 or COOR' group, and

R' is R, H, A, aryl, alkylaryl or alkynyl,

where L, R and R' may each, independently of one another, adopt identical or different meanings in different positions of the molecule,

and

A is straight-chain or branched C1-C30-alkyl, C3-C30-cycloalkyl, straight-chain or branched C2-C30-alkenyl or straight-chain or branched C3-C30-cycloalkenyl,

aryl is C6-C10-aryl or alkylaryl,

alkylaryl is C7-C18-alkylaryl,

alkynyl is straight-chain or branched C2-C30-alkynyl.

2. (Currenlty amended) A compound ~~Compounds~~ according to Claim 1, in which

A is straight-chain or branched C1-C9-alkyl, straight-chain or branched C3-C9-cycloalkyl, straight-chain or branched C2-C9-alkenyl or straight-chain or branched C3-C9-cycloalkenyl,

aryl is phenyl or naphthyl,

alkylaryl is tolyl or mesityl,

alkynyl is straight-chain or branched C2-C9-alkynyl,

and R and R' may each, independently of one another, adopt identical or different meanings in different positions of the molecule.

3. (Currently amended) A compound ~~Compounds~~ according to Claim 1, in which

A is ~~straight-chain or branched C1-C4-alkyl from the group consisting of~~ methyl, ethyl, n- and i-propyl and n-, i- ~~and~~ tert-butyl, ~~C3-C6-cycloalkyl from the group consisting of~~ cyclopropyl, cyclobutyl, cyclopentyl, ~~and~~ cyclohexyl, ~~straight-chain or branched C2-C6-alkenyl from the group consisting of~~ vinyl C2-C6-alkenyl, propenyl, butenyl, pentenyl, ~~and~~ hexenyl, ~~or C3-C6-cycloalkenyl from the group consisting of~~ cyclopropenyl, cyclobutenyl, cyclopentenyl, cyclopentadienyl ~~and~~ or methylcyclopentadienyl,

aryl is phenyl or naphthyl,

alkylaryl is tolyl or mesityl,

alkynyl is ~~straight-chain or branched C2-C6-alkynyl from the group consisting of~~ ethynyl, propynyl, butynyl, pentynyl ~~and~~ or hexynyl,

and R and R' may each, independently of one another, adopt identical or different meanings in different positions of the molecule.

4. (Currenlty amended) A compound ~~Compounds~~ according to Claim 1, in which L is R-C≡C-R' or R'HC=CHR, each having at least one silyl or ester group, and the radicals R and R` are as defined in Claim 1.

5. (Currenlty amended) A compound ~~Compounds~~ according to Claim 1, in which L is R`$_3$Si-C≡C-R`, where R' is $SiMe_3$, CH_3, C_2H_5, C_3H_7, C_4H_9, phenyl, COOMe or COOEt.

6. (Currenlty amended) A compound ~~Compounds~~ according to Claim 1, in which L is ~~an alkyne selected from the group consisting of~~ $Me_3SiC≡C$-$SiMe_3$, Me_3Si-C≡C-^{n}Bu, McOOC-C≡C-COOMe, EtOOC-C≡C-COOEt ~~and~~ or Me_3Si-C≡C-R', in which R' is CH_3, C_2H_5, C_3H_7, phenyl, COOMe or COOEt.

7. (Currenlty amended) A compound ~~Compounds~~ according to Claim 1, in which L is ~~an alkene selected from the group consisting of~~ H_2C=CHSiMe_3, H_2C=CHCOOCH_3, H_2C=CHCOOC_2H_5 ~~and~~ or H_2C=CHSiR'$_3$, in which R', independently of one another, is CH_3, C_2H_5, C_3H_7, C_4H_9, HC=CH_2 or phenyl.

8. (Currenlty amended) A compound ~~Compounds~~ according to Claim 1, in which L is ~~a compound selected from the group consisting of~~ CH_3-C≡N, ^{t}Bu C≡N, C_4H_9C≡N, Ph-C≡N; N(CH_3)$_3$, N(C_2H_5)$_3$, H_2N-(CH_2)$_2$-NH_2, (CH_3)$_2$N-(CH_2)$_2$-N(CH_3)$_2$, (C_2H_5)$_2$N-(CH_2)$_2$-N(C_2H_5)$_2$, H_2N-(CH_2)$_4$-NH_2, (CH_3)$_2$N-(CH_2)$_4$-N(CH_3)$_2$, (C_2H_5)$_2$N-(CH_2)$_4$N(C_2H_5)$_2$, 2,9-dimethyl-1,10-phenanthroline; P(OCH_3)$_3$, P(OC_2H_5)$_3$, P(OC_6H_{11})$_3$, P(OPh)$_3$; P(CH_3)$_3$, P(C_2H_5)$_3$, P(C_3H_7)$_3$, P(C_4H_9)$_3$, P(C_6H_{11})$_3$; C_2H_5-O-C_2H_5, CH_3-O-C_4H_9, CH_3O-(CH_2)$_2$-OCH_3, $C_2H_5$0-(CH_2)$_2$-OC_2H_5, CH_3-S-CH_3, C_2H_5-S-C_2H_5, C_3H_7-S-C_3H_7, Ph-S-Ph, CH_3S-(CH_2)$_2$-SCH_3, CH_3S-(CH_2)$_3$-SCH_3, C_2H_5S-(CH_2)$_2$-SC_2H_5 ~~and~~ or PhS-(CH_2)$_2$-SPh.

9. (Currenlty amended) A compound ~~Compounds~~ of ~~the general~~ formula (I) di{[bis(trimethylsilyl)acetylene]copper(I)} oxalate,

di{[(trimethylsilyl)(n-butyl)acetylene]copper(I)} oxalate,
di[(vinyl-t-butyldimethylsilane)copper(I)] oxalate,
di[(vinyldiethylmethylsilane)copper(I)] oxalate.

10. (Currently Amended) A process ~~Process~~ for the preparation of ~~the~~ a compound ~~compounds~~ of the general formula (I) according to Claim 1, ~~characterised in that~~ comprising reacting Cu_2O ~~is reacted~~ with oxalic acid and a Lewis base L in an inert solvent, and isolating the resultant product ~~is isolated~~.

11. (Currently Amended) A process ~~Process~~ according to Claim 10, wherein ~~characterised in that~~ an inert aprotic organic solvent is used which is an open-chain or cyclic aliphatic or aromatic hydrocarbon, a halogenated aliphatic or halogenated aromatic hydrocarbon or a linear or cyclic ether or a mixture of these hydrocarbons.

12. (Currently Amended) A process ~~Process~~ according to Claim 10, ~~characterised in that~~ - further comprising ~~the~~ utilizing a solvent which is ~~selected from the group consisting of~~ pentane, hexane, heptane, cyclohexane, toluene, methylene chloride, trichloromethane, chlorobenzene, diethyl ether ~~and~~ or tetrahydrofuran ~~is used~~.

13. (Currently Amended) A process ~~Process~~ according to Claim 10, ~~characterised in that it is~~ carried out under a protective-gas atmosphere.

14. (Currently Amended) A process ~~Process~~ according to Claim 13, wherein ~~characterised in that~~ the protective gas employed is nitrogen or argon.

15. (Currently Amended) A process ~~Process~~ according to Claim 10, wherein ~~characterised in that~~ the Lewis base L is employed in at least twice the stoichiometric ratio ~~excess relative to the stoichiometric ratio~~ of the starting materials Cu_2O and oxalic acid [,] ~~but at least in twice the stoichiometric~~

~~ratio~~.

16. (Currently Amended) A process ~~Process~~ according to Claim 10, wherein ~~characterised in that~~ the starting materials Cu_2O, oxalic acid and Lewis base L are employed in a stoichiometric ratio of from 1 : 1 : 2 to 1 : 1 : 4.

17. (Currently Amended) A process ~~Process~~ according to Claim 10, wherein ~~characterised in that~~ two different Lewis bases L are employed in identical molar amounts.

18. (Currently Amended) A process ~~Process~~ according to Claim 10, wherein ~~characterised in that~~ the reaction is carried out within a reaction time of from about 1 to 24 hours at a temperature in the range from about -30 to +100°C.

19. (Currently Amended) A process ~~Process~~ according to Claim 10, ~~characterised in that it is~~ carried out at room temperature.

20. (Currently Amended) A process ~~Process~~ according to Claim 10, wherein ~~characterised in that~~ , when the reaction is complete, insoluble constituents are separated off, and the reaction product is isolated from the solution and, if necessary, purified, or in that the reaction product is separated from the reaction mixture by extraction, isolated and, if necessary, purified.

21. (Currently Amended) A process ~~Process~~ according to Claim 10, wherein ~~characterised in that~~ insoluble constituents are separated off by filtration.

22. (Cancelled)

23. (Currently Amended) ~~Process~~ A process for the production of highly pure, thin metallic copper layers, ~~characterised in that~~ wherein compounds of ~~the general~~

metallic copper layers, ~~characterised in that~~ wherein compounds of ~~the general~~ formula (I) according to Claim 1 are heated, causing elimination of the Lewis base L and deposition of metallic copper deposited through decarboxylation.

24. (Currently Amended) ~~Process~~ A process according to Claim 23, ~~characterised in that~~ wherein the elimination of the Lewis base L is carried out at a temperature in the range from about 50 to about 200°C, and the decarboxylation is completed at a temperature in the range from about 150 to 350°C with formation of metallic copper.

25. (Currently Amended) ~~Process~~ A process according to Claim 23, ~~characterised in that~~ wherein the Lewis base L eliminated is recycled and, re-employed in a process for preparing compounds of general formula (I) by reacting Cu_2O with oxalic acid and the Lewis base in an inert solvent and isolating the product, and then ~~using~~ the resultant compounds of ~~general~~ formula (I) are used for the production of highly pure, thin metallic copper layers.

26. (Cancelled)